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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q67528

Noriaki SAITO, et al.

Appln. No.: 10/000,364

Group Art Unit: 1711

Confirmation No.: 9783

Examiner: Duc Truong

Filed: December 4, 2001

For: METHOD OF PRODUCING NOVOLAK RESIN

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

MAIL STOP ISSUE FEE

Director of the U.S. Patent and Trademark Office
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

The Examiner, in the Notice of Allowance dated January 28, 2005, included a *Statement of Reasons for Allowance* that indicated:

none of the prior art discloses or suggests the method of reacting an ortho-cresol and an aldehyde using an oxalic acid at 110 °C to 160 °C under pressure in the claimed method of producing a phenol novolak resin having an ortho ratio of *greater than 30%*.

However, Applicants respectfully submit that the Examiner's *Statement of Reasons for Allowance* is inaccurate.

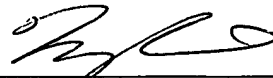
Specifically, present Claim 1 recites "a method of producing a phenol novolak resin having an ortho ratio of *30% or more*," which includes a phenol novolak resin having an ortho ratio of 30% *and* a phenol novolak resin having an ortho ratio of greater than 30%.

Comments on Statement of Reasons for Allowance
U.S. Appln. No.: 10/000,364

Attorney Docket Q67528

Applicants respectfully submit that Claims 1, 2 and 4 are patentable over the references of record by virtue of their own claim language, and not the paraphrase included in the Examiner's statement.

Respectfully submitted,



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CUSTOMER NUMBER

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